		#	116.3	SHEET 1 OF
FORM PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. ASMINT.055AUS	APPLICATION NO. **10/890,215	
Z	DISCLOSURE STATEMENT			
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118.00				U.S. PATENT DOCUMENTS		J	
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g	3	4,374,158	2/15/83	Taniguchi et al.		_	
E	4	4,377,347	3/22/83	Hanmyo et al.	1	_	
El	5	4,389,967	6/28/83	Shimoda et al.	_		
8	6	4,428,975	1/31/84	Dahm et al.	_	-	
Se	7	4,499,354	2/12/85	Hill et al.	_	-	
લી	8	4,522,849	6/11/85	Lewandowski	-	_	
50	9	4,592,307	6/3/86	Jolly		_	
CO	10	4,633,051	12/30/86	Olson	_	_	
8	11	4,653,428	3/31/87	Wilson et al.	_	_	
R	12	4,692,556	9/8/87	Bollen et al.		_	
4	13	4,976,996	12/11/90	Monkowski et al.		_	•
Ŕ	14	4,978,567	12/18/90	Miller	_		
Q	15	4,984,904	1/15/91	Nakano et al.	_	_	
28	16	5,027,746	7/2/91	Frijlink	_		
70	17	5,065,698	11/19/91	Koike	_	_	
B	18	5,104,514	4/14/92	Quartarone	_	_	
4	19	5,128,958	7/14/92	Nagashima et al.	_	-	
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E	21	5,271,967	12/21/93	Kramer et al.	_		
Źſ	22	5,315,092	5/24/94	Takahashi et al.		_	
8°	23	5,336,327	8/9/94	Lee	_	~	i
4	24	5,360,269	11/1/94	Ogawa et al.	—	~	
(C)	25	5,421,893	6/6/95	Perlov	-		
4	26	5,456,761	10/10/95	Auger et al.	=	-	
જ	27	5,474,618	12/12/95	Allaire	-	-	

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FORM PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. ASMINT.OSSAUS	APPLICATION NO. "10/590,215
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EP	29	5,514,439	5/7/96	Sibley	_	_	
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50	39	6,056,823	5/2/00	Sajoto et al.	_	-	
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		SHEET 3 OF 3
	ENT OF COMMERCE TRADEMARK OFFICE ASMINT.055AUS	APPLICATION NO. "10/690,215
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INITIAL							YES	МО
. 20	50	WO 95/31582	11/23/95	PCT		_		
EP	51	WO 97/06288	2/20/97	PCT				
EP	52	WO 99/23276	5/14/99	PCT		-		
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8	54	Linke et al., "Behavior of Boron-Doped Graphites, Plasma-Sprayed B ₄ C ₁ and a-C/B:H as Plasma-Facing Materials," Fusion Technology, Vol. 20, (September 1991), pp. 227-230.
8	55	Moslehi et al., "Compositional Studies of Thermally Nitrided Silicon Dioxide (Nitroxide)," <i>J. Electrochem Soc.</i> , Vol. 132, No. 9, pp. 2189-2197 (September 1985).
50	56	Murarka et al., "Thermal Nitridation of Sillcon in Ammonia Gas: Composition and Oxidation Resistance of the Resulting Films," J. Electrochem. Soc., Vol. 126, No. 6, pp. 998-1003 (June 1979).
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ATTY, DOCKET NO. ASMINT,055AUS	APPLICATION NO. 10/890,215	
APPLICANT Timmermans et al.		

GROUP 2912

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U.S. DEPARTMENT OF COMMERCE

INFORMATION DISCLOSURE STATEMENT
BY APPLICANT

(USE SEVERAL SHEETS IF NECESSARY)

PATENT AND TRADEMARK OFFICE

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FORM PTO-1449,

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DATE CONSIDERED

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